酸性塩化浴Zn-Ni-SiO_2複合めっき液
Chloride-based Acidic Zinc-nickel-silica Composite Plating Solution

ニコジンクACS
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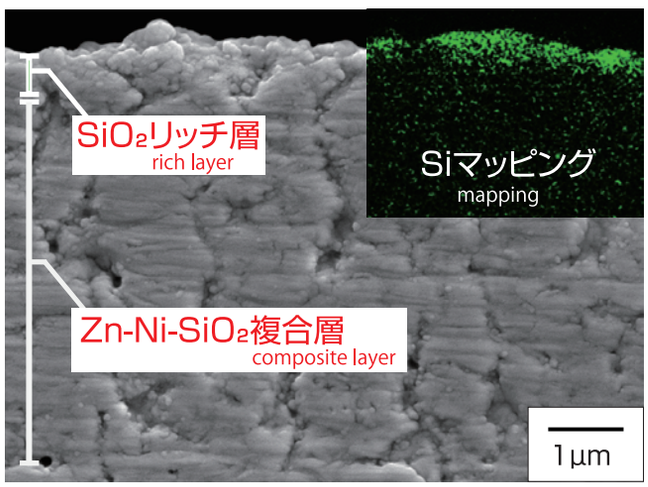
●水素脆性が少なく、熱処理時間を短縮
Small hydrogen embrittlement, shorten heat treatment time

●高い析出速度(2A/dm²：0.4μm/min)と電流効率(80%)
High deposition rate　High current efficiency

●幅広い電流密度範囲で安定した合金比率(Ni:12～15wt%)
Obtain stable alloy ratio at wide current density area

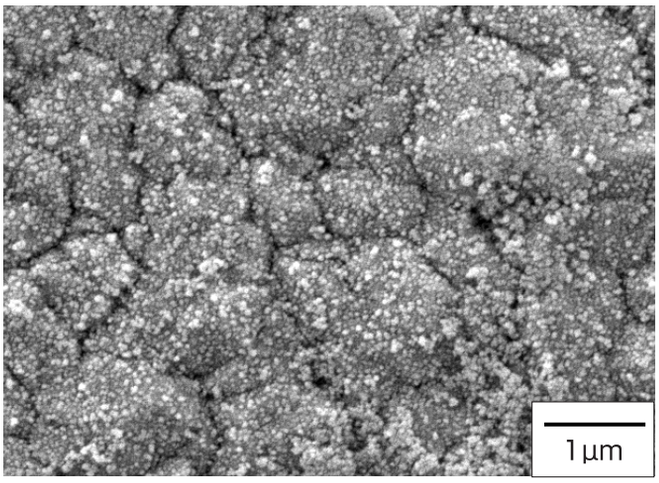
●高硬度(Hv450)で低いトルク係数
High hardness, low torque coefficient

多孔性皮膜が水素を放出
Porous film releases hydrogen



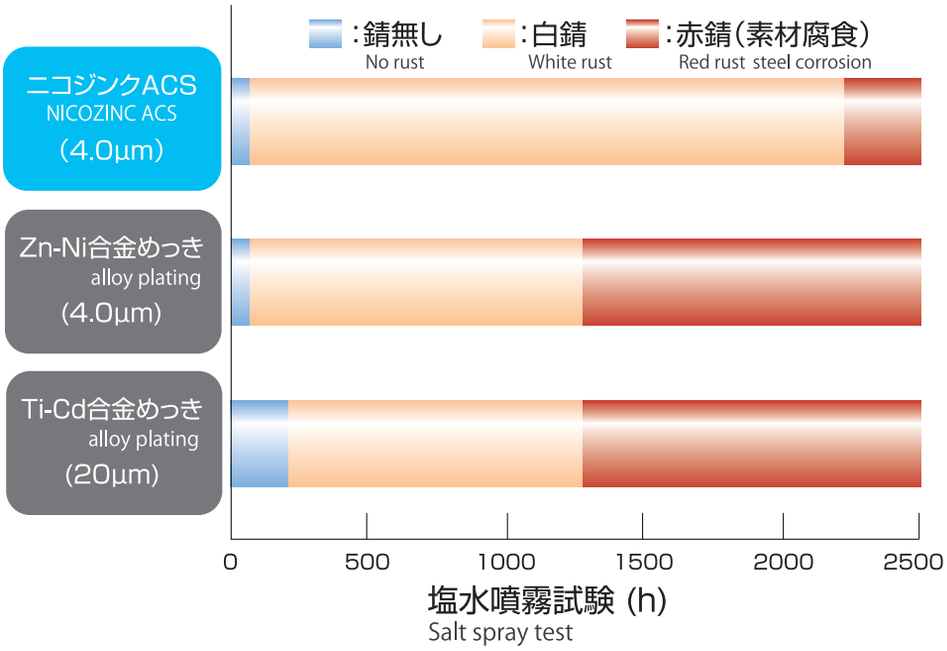
断面SEM像
SEM image (cross-section)

SiO_2粒子が表面に多く共析
Rich SiO_2 particles on surfaces



表面SEM像
SEM image (surface)

優れた耐食性
High corrosion resistance



標準処理条件
Standard condition

pH	2.0
浴温 Bath temperature	40℃
電流密度 Current density	2A/dm²
撹拌 Agitation	空気撹拌 Air agitation
陽極 Anode	ニッケル Nickel
陰極 Cathode	鉄鋼 Steel